

COPY

SHEET 1 of 2

INFORMATION DISCLOSURE CITATION PTO-1449		Atty. Docket No.		Serial No.		
		NTI-022		10/003,358		
		Applicant				
		CHANG, Fang-Cheng				
		Filing Date		Group		
		11/14/2001		2431 2825		
U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
JSR	5,282,140	1/25/1994	Tazawa, et al.	364	468	6/24/1992
	6,130,750	10/10/2000	Ausschnitt, et al.	356	401	8/28/1997
	6,225,025 B1	5/1/2001	Hoshino	430	296	9/22/1998
	6,339,836 B1	1/15/2002	Eisenhofer, et al.	716	5	8/24/1998
JSR	6,346,426 B1	2/12/2002	Toprac, et al.	438	8	11/17/2000

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EXAMINER:

Fang-Cheng Chang

Date Considered:

8-8-05

EXAMINER: Initial if reference considered, whether or not citation is in conformance with
MPEP § 609; draw line through citation if not in conformance and not considered. Include
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SHEET 2 of 2

INFORMATION DISCLOSURE CITATION PTO-1449	Atty. Docket No. NTI-022	Serial No. 10/003,358
	Applicant CHANG, Fang-Cheng	
	Filing Date 11/14/2001	Group 2154 2825
	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
EXAMINER'S INITIALS	CITATION	
JSA	Lin, B.J., et al., "Single-Level Electric Testsites for Phase-Shifting Masks", SPIE, Vol. 1673, pp. 221-228, March 9-11, 1992.	
	Cobb, N., "Fast Optical and Process Proximity Correction Algorithms for Integrated Circuit Manufacturing", Dissertation, University of California at Berkeley, UMI Microform 9902038 (139 pages).	
	Uhling, W., et al., "Model of an Instrumented Opto-Electronic Transmission System in HDL-A and VHDL-AMS", SPIE, Vol. 3893, pp. 137-146, October 1999.	
JSA	Granik, Y., et al., "Sub-Resolution Process Windows And Yield Estimation Technique Based On Detailed Full-Chip CD Simulation", SPIE, Vol. 4182, pp. 335-341 (2000).	

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NTI Use Only: 749; 226; 1